

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently Amended) An apparatus for treating a workpiece with a plasma, comprising:
 - a chamber having a processing space;
 - a gas supply port in said chamber for introducing a process gas into said processing space;
 - ~~a vacuum port in said chamber for evacuating said processing space;~~
 - ~~a workpiece holding~~ workpiece holding portion positioned in said processing space and configured for holding the workpiece;
 - a plasma excitation source operable for exciting the process gas in said processing space to generate a plasma;
 - ~~an electrically insulated vacuum distribution baffle positioned between said vacuum port and said workpiece holding portion; and~~
 - a powered electrode electrically connected to said plasma excitation source and said workpiece-holding portion ~~and positioned between said vacuum distribution baffle and said workpiece holding portion, said~~;
 - a vacuum port in said chamber for evacuating said processing space, said vacuum port being located in said chamber below said powered electrode, and said vacuum port having a centerline oriented substantially perpendicular to said powered electrode; and

a vacuum distribution baffle positioned between below said powered electrode and above
said vacuum port for uniformly dispersing process gas across said powered electrode, said
vacuum distribution baffle operating [[to]] for electrically shield shielding said powered
electrode from said chamber and for preventing plasma generation in a portion of said processing
space between said vacuum distribution baffle and said vacuum port.

2. (Currently Amended) The apparatus of claim 1, wherein said powered electrode is part of an assembly which includes said ~~workpiece holding~~ workpiece holding portion.
3. (Currently Amended) The apparatus of claim 1, wherein said ~~workpiece holding~~ workpiece holding portion includes first and second side rails that are adjustable in width to accommodate workpieces of different widths positioned therebetween.
4. (Currently Amended) The apparatus of claim 1, wherein the chamber further comprises a lid, [[and]] a lower chamber portion, and a sealing member therebetween between said lid and said
lower chamber portion, said lid movable relative to said lower chamber portion between an open
position and a closed position in which said sealing member forms a seal between said lid and
said lower chamber portion, said lid being connected to said lower chamber portion by a hinge
having at least one obround bearing groove a slotted opening and a hinge pin positioned in said
slotted opening, said slotted opening oriented such that said lid moves vertically relative to said
lower chamber portion for accommodating substantially vertical compression of compressing
said sealing member [[as]] when said lid is in the closed position and said processing space is
evacuated through said vacuum port

5. (Original) The apparatus of claim 1 further comprising a ground electrode positioned on an opposite side of said workpiece holding portion relative to said powered electrode.

6. (Previously Presented) The apparatus of claim 5, wherein said powered electrode and said ground electrode are approximately equidistant from said workpiece holding portion, said electrodes producing an electric field substantially perpendicular to the workpiece when said workpiece is held in said workpiece holding portion.

7. (Previously Presented) The apparatus of claim 6, wherein said chamber includes a lid movable between open and closed positions for accessing said workpiece holding portion, said lid further comprising said ground electrode.

8. (Cancelled)

9. (Currently Amended) The apparatus of claim 1, wherein said chamber includes a lid movable between open and closed positions for accessing said workpiece holding portion, and said [[said]] gas supply port is positioned in said lid for introducing the process gas to said processing space.

10. (Previously Presented) The apparatus of claim 9, wherein said lid includes an interior surface facing said workpiece holding portion of said processing space when said lid is in said closed position, and said gas supply port further comprises a gas distribution space within said

lid and an array of apertures on said interior surface configured to uniformly distribute the process gas from said gas distribution space onto the workpiece.

11. (Currently Amended) An apparatus for treating a workpiece with plasma, comprising:

a chamber having a chamber base, an access member movable relative to said chamber base between an open position and a closed position, a processing space defined inside said chamber and configured to hold the workpiece, and a sealing member between said chamber base and said movable access member to seal said processing space when said access member is in said closed position;

a gas supply port in said chamber for introducing a process gas into said processing space;

an electrode assembly positioned within said chamber and electrically coupled with said workpiece holding portion;

a plasma excitation source operably connected to said electrode assembly for exciting the process gas within said processing space to generate a plasma;

a vacuum port in said chamber for evacuating said processing space; and

a hinge coupling said chamber base to said access member, said hinge including ~~at least one obround bearing groove~~ a slotted opening and a hinge pin positioned in said slotted opening, said slotted opening oriented such that said access member moves vertically relative to said chamber base for accommodating substantially vertical compression of uniformly compressing said sealing member [[as]] when said access member is in the closed position and said processing space is evacuated through said vacuum port.

12. (Previously Presented) The apparatus of claim 11, wherein said sealing member is electrically conductive so that said access member and said chamber base are in electrical continuity when said access member is in said closed position.

13. (Cancelled)

14. (Previously Presented) An apparatus for processing a workpiece with a plasma, comprising:

- a chamber having a processing space and a workpiece holding portion configured to hold the workpiece in said processing space;
- a gas supply port in for introducing a process gas into said processing space;
- a vacuum port in said chamber for evacuating said processing space;
- a powered electrode positioned on one side of said workpiece holding portion;
- a plasma excitation source operably connected to said powered electrode assembly for exciting the process gas within said processing space to generate a plasma; and
- a ground electrode positioned on an opposite side of said workpiece holding portion relative to said powered electrode, said powered electrode and said ground electrode being approximately equidistant from said workpiece holding portion, and said powered and ground electrodes together producing an electric field substantially perpendicular to said workpiece for exciting the process gas when the workpiece is held in said workpiece holding portion.

15. (Previously Presented) The apparatus of claim 14, wherein said chamber includes a lid movable between open and closed positions for accessing said workpiece holding portion of said processing space, said lid further comprising said ground electrode.

16. (Previously Presented) The apparatus of claim 15, wherein said lid further includes a gas supply port for introducing the process gas to said processing space.

17. (Previously Presented) The apparatus of claim 16, wherein said lid includes an interior surface facing said workpiece holding portion of said processing space when said lid is in said closed position, and said gas supply port further comprises a gas distribution space within said lid and an array of apertures on said interior surface configured to uniformly distribute the process gas from said gas distribution space across the workpiece.

18-43. (Cancelled)

44. (Previously Presented) The apparatus of claim 1 wherein said chamber includes a wall, and further comprising:

an electrical feedthrough extending through said wall of said chamber and electrically coupled with said powered electrode.

45. (Previously Presented) The apparatus of claim 44 wherein said electrical feedthrough extends through said vacuum distribution baffle.

46. (New) The apparatus of claim 1 wherein said plate is electrically-insulated.

47. (New) The apparatus of claim 46 wherein said plate is formed from an electrically-

insulating material.

48. (New) The apparatus of claim 47 wherein said electrically-insulating material is a ceramic.

49. (New) The apparatus of claim 1 wherein said vacuum distribution baffle includes a plate having a plurality of orifices that permit the process gas to flow from said gas supply port to said vacuum port.

50. (New) The apparatus of claim 49 wherein said chamber includes a chamber base, said plate is positioned between said chamber base and said powered electrode, said powered electrode includes a perimeter, and said vacuum port is symmetrically positioned in said chamber base relative to said perimeter.

51. (New) The apparatus of claim 49 wherein said plate is imperforated other than said orifices.

52. (New) The apparatus of claim 1 wherein said powered electrode is located below said gas supply port.

53. (New) The apparatus of claim 1 wherein said vacuum port is centrally located in said chamber below said powered electrode.